

Pt. 63, Subpt. MMM, Table 2

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Reference to subpart A	Applies to subpart MMM	Explanation
§ 63.7(e)(2)	Yes	Except § 63.1365 specifies less than 3 runs for certain tests.
§ 63.7(e)(3)	Yes	
§ 63.7(e)(4)	Yes	
§ 63.7(f)	Yes	Except § 63.1368(a) specifies that the results of the performance test be submitted with the Notification of Compliance Status report
§ 63.7(g)(1)	Yes	
§ 63.7(g)(2)	N/A	
§ 63.7(g)(3)	Yes	Reserved.
§ 63.7(h)	Yes	
§ 63.8(a)(1)–(2)	Yes	
§ 63.8(a)(3)	N/A	Reserved.
§ 63.8(a)(4)	Yes	
§ 63.8(b)(1)	Yes	
§ 63.8(b)(2)	No	§ 63.1366 specifies CMS requirements. Except the submittal date of the immediate startup, shutdown, and malfunction reports for CMS events shall be 2 days as in § 63.6(e)(3)(iv).
§ 63.8(b)(3)–(c)(3)	Yes	
§ 63.8(c)(4)	No	
§ 63.8(c)(5)–(8)	No	§ 63.1366 specifies monitoring frequencies.
§ 63.8(d)–(f)(3)	Yes	
§ 63.8(f)(4)	Yes	
§ 63.8(f)(5)	Yes	Except § 63.1368(b) specifies that requests may also be included in the Precompliance report.
§ 63.8(f)(6)	No	
§ 63.8(g)	No	
§ 63.9(a)–(d)	Yes	Subpart MMM does not require CEM's.
§ 63.9(e)	No	
§ 63.9(f)	No	
§ 63.9(g)	No	Subpart MMM does not contain opacity and visible emission standards.
§ 63.9(h)(1)	Yes	
§ 63.9(h)(2)(i)	Yes	
§ 63.9(h)(2)(ii)	No	Except § 63.1368(a)(1) specifies additional information to include in the Notification of Compliance Status report.
§ 63.9(h)(3)	Yes	
§ 63.9(h)(4)	N/A	
§ 63.9(h)(5)–(6)	Yes	§ 63.1368 specifies the Notification of Compliance Status report is to be submitted within 150 days after the compliance date.
§ 63.9(i)	Yes	
§ 63.9(j)	No	
§ 63.10(a)–(b)(1)	Yes	§ 63.1368(h) specifies procedures for notification of changes.
§ 63.10(b)(2)	No	
§ 63.10(b)(3)	Yes	
§ 63.10(c)	Yes	§ 63.1367 specifies recordkeeping requirements.
§ 63.10(d)(1)	Yes	
§ 63.10(d)(2)	Yes	
§ 63.10(d)(3)	No	Subpart MMM does not include opacity and visible emission standards.
§ 63.10(d)(4)	Yes	
§ 63.10(d)(5)	Yes	
§ 63.10(e)(1)–(2)(i)	Yes	Except that actions and reporting for batch processes do not apply during start-up and shutdown.
§ 63.10(e)(2)(ii)	No	
§ 63.10(e)(3)	Yes	
§ 63.10(e)(4)	No	Subpart MMM does not include opacity monitoring requirements.
§ 63.10(f)	Yes	
§ 63.11–§ 63.15	Yes	

[64 FR 33589, June 23, 1999, as amended at 67 FR 59355, Sept. 20, 2002]

TABLE 2 TO SUBPART MMM OF PART 63—STANDARDS FOR NEW AND EXISTING PAI SOURCES

Emission source	Applicability	Requirement
Process vents	Existing: Processes having uncontrolled organic HAP emissions ≥ 0.15 Mg/yr. Processes having uncontrolled HCl and chlorine emissions ≥ 6.8 Mg/yr. Individual process vents meeting flow and mass emissions criteria that have gaseous organic HAP emissions controlled to less than 90% on or after November 10, 1997.	90% for organic HAP per process or to outlet concentration of ≤ 20 ppmv TOC. 94% for HCl and chlorine per process or to outlet HCl and chlorine concentration of ≤ 20 ppmv. 98% gaseous organic HAP control per vent or ≤ 20 ppmv TOC outlet limit.

Environmental Protection Agency

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Emission source	Applicability	Requirement
	New: Processes having uncontrolled organic HAP emissions ≥ 0.15 Mg/yr. Processes having uncontrolled HCl and chlorine emissions ≥ 6.8 Mg/yr and < 191 Mg/yr. Processes having uncontrolled HCl and chlorine emissions ≥ 191 Mg/yr.	98% for organic HAP per process or ≤ 20 ppmv TOC. 94% for HCl and chlorine per process or to outlet concentration of ≤ 20 ppmv HCl and chlorine. 99% for HCl and chlorine per process or to outlet concentration of ≤ 20 ppmv HCl and chlorine.
Storage vessels	Existing: ≥ 75 m ³ capacity and vapor pressure ≥ 3.45 kPa. New: ≥ 38 m ³ capacity and vapor pressure ≥ 16.5 kPa. ≥ 75 m ³ capacity and vapor pressure ≥ 3.45 kPa	Install a floating roof, reduce HAP by 95% per vessel, or to outlet concentration of ≤ 20 ppmv TOC. Same as for existing sources.
Wastewater ^a	Existing: Process wastewater with $\geq 10,000$ ppmw Table 9 compounds at any flowrate or $\geq 1,000$ ppmw Table 9 compounds at ≥ 10 L/min, and maintenance wastewater with HAP load ≥ 5.3 Mg per discharge event. New: Same criteria as for existing sources	Same as for existing sources. Reduce concentration of total Table 9 compounds to < 50 ppmw (or other options).
Equipment leaks	Total HAP load in wastewater POD streams $\geq 2,100$ Mg/yr.. Subpart H	Reduce concentration of total Table 9 compounds to < 50 ppmw (or other options). 99% reduction of Table 9 compounds from all streams. Subpart H with minor changes, including monitoring frequencies consistent with the proposed CAR.
Product dryers and bag dumps.	Dryers used to dry PAI that is also a HAP, and bag dumps used to introduce feedstock that is a solid and a HAP.	Particulate matter concentration not to exceed 0.01 gr/dscf.
Heat exchange systems	Each heat exchange system used to cool process equipment in PAI manufacturing operations.	Monitoring and leak repair program as in HON.

^a Table 9 is listed in the appendix to subpart G of 40 CFR part 63.

TABLE 3 TO SUBPART MMM OF PART 63—MONITORING REQUIREMENTS FOR CONTROL DEVICES ^A

Control device	Monitoring equipment required	Parameters to be monitored	Frequency
All control devices	1. Flow indicator installed at all bypass lines to the atmosphere and equipped with continuous recorder or. 2. Valves sealed closed with car-seal or lock-and-key configuration.	1. Presence of flow diverted from the control device to the atmosphere or. 2. Monthly inspections of sealed valves.	Hourly records of whether the flow indicator was operating and whether a diversion was detected at any time during each hour. Monthly.
Scrubber	Liquid flow rate or pressure drop mounting device. Also a pH monitor if the scrubber is used to control acid emissions..	1. Liquid flow rate into or out of the scrubber or the pressure drop across the scrubber.. 2. pH of effluent scrubber liquid.	1. Every 15 minutes. 2. Once a day.
Thermal incinerator	Temperature monitoring device installed in firebox or in ductwork immediately downstream of firebox ^b .	Firebox temperature	Every 15 minutes.
Catalytic incinerator	Temperature monitoring device installed in gas stream immediately before and after catalyst bed.	Temperature difference across catalyst bed.	Every 15 minutes.
Flare	Heat sensing device installed at the pilot light.	Presence of a flame at the pilot light.	Every 15 minutes.
Boiler or process heater < 44 megawatts and vent stream is not mixed with the primary fuel.	Temperature monitoring device installed in firebox ^b .	Combustion temperature	Every 15 minutes.